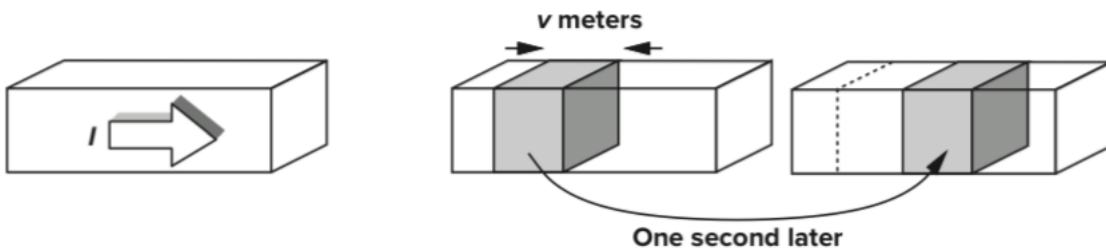


Derivation of I-V characteristics: relationship between drain-current & its terminal voltage (MOSFET)

* Consider a semiconductor bar carrying a current I .

$Q_d \rightarrow$ mobile charge density along the dir² of current in coulombs/meter
 $v \rightarrow$ velocity of charge in m/sec.

$$I = Q_d \cdot v \longrightarrow \text{why}$$



charge enclosed in 'v' meters of the box must flow through section in 1 second
 total charge in 'v' meters = $Q_d v$

* Consider NFET whose S & D are connected to ground.

→ onset of inversion occurs @ $V_{GS} = V_{TH}$

→ inversion charge density produced by gate-oxide capacitance $\propto V_{GS} - V_{TH}$

→ for $V_{GS} \geq V_{TH}$

$$Q_d = \underbrace{WC_{ox}}_{\text{total capacitance/unit length}} (V_{GS} - V_{TH})$$

→ if $V_d > 0$

channel potential

Source
0

Drain
 V_D

local voltage difference
b/w gate & channel

V_G

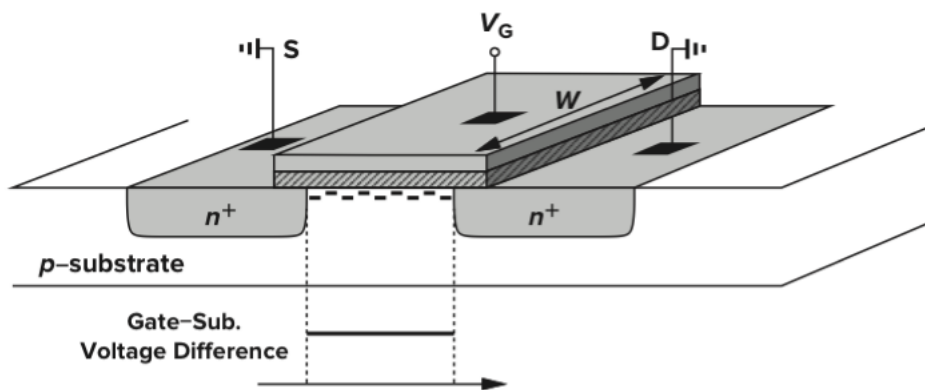
$V_G - V_D$

$$Q_d(x) = WC_{ox} [V_{GS} - V_x - V_{TH}]$$

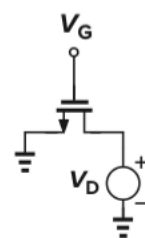
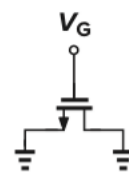
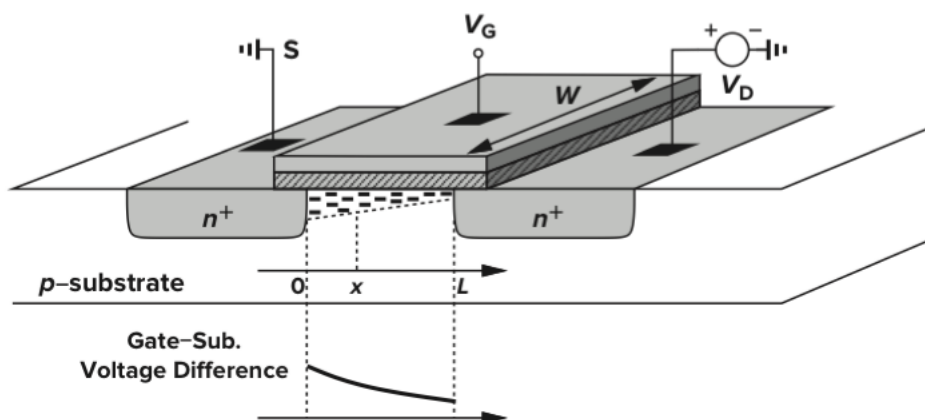
↓
channel potential at x.

↑ charge carriers
are -ve

$$I_D = -WC_{ox} [V_{GS} - V(x) - V_{TH}] v$$



(a)



for semiconductors,

$$v = \mu E$$

velocity of charge = mobility of charge carrier $\times \vec{E}$

$$E(x) = -\frac{dV}{dx}$$

$$\text{So, } I_D = W C_{ox} [V_{GS} - V(x) - V_{TH}] \mu_n \frac{dV(x)}{dx}$$

boundary conditions $V(0) = 0$
 $V(L) = V_{DS}$

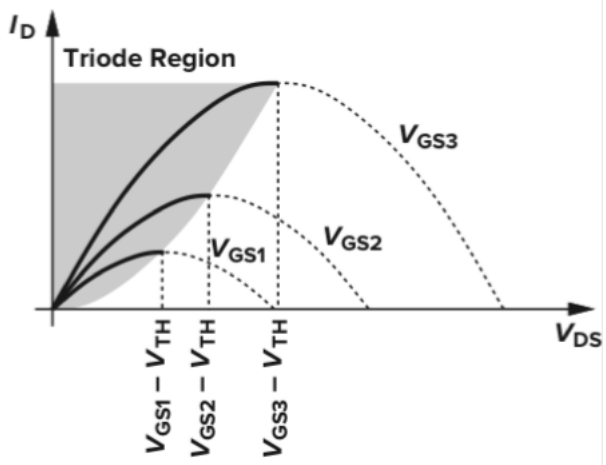
$$\int_{x=0}^L I_D dx = \int_{V=0}^{V_{DS}} W C_{ox} \mu_n [V_{GS} - V(x) - V_{TH}] dV$$

I_D is constant along channel.

$$I_D = \mu_n C_{ox} \frac{W}{L} \left[(V_{GS} - V_{TH}) V_{DS} - \frac{1}{2} V_{DS}^2 \right]$$

↓
effective channel length.

Let's plot I_D vs V_{DS} for different values of V_{GS} ,



Observations:

1. Current capability of device increases with V_{GS}

2. Peak of each parabola occurs @
 $V_{DS} = V_{GS} - V_{TH}$

3. Peak current

$$I_D(\text{max}) = \frac{1}{2} \mu_n C_{ox} \underbrace{\frac{W}{L}}_{\text{Aspect ratio}} \underbrace{(V_{GS} - V_{TH})^2}_{\text{Overdrive Voltage}^2}$$

4. If $V_{DS} \leq V_{GS} - V_{TH}$
device operates in "triode region"

5. If $V_{DS} \ll 2(V_{GS} - V_{TH})$, we have

$$I_D = \mu_n C_{ox} \frac{W}{L} \left[(V_{GS} - V_{TH}) V_{DS} - \frac{1}{2} V_{DS}^2 \right]$$



$$I_D \approx \mu_n C_{ox} \frac{W}{L} (V_{GS} - V_{TH}) V_{DS}$$

6. for small V_{DS} ,

each parabola \approx st. line

path from $S \rightarrow D \approx$ linear resistor

$$V = IR$$
$$R = \frac{V}{I}$$

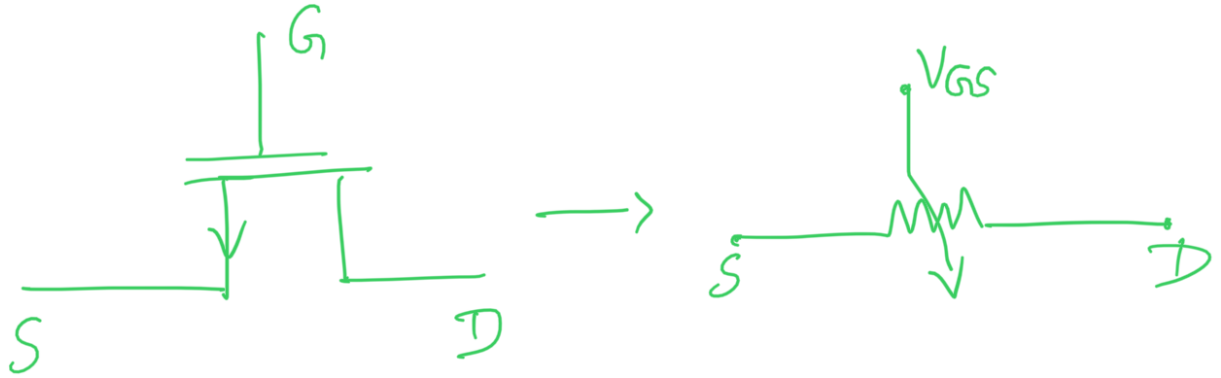
$$R_{on} = \frac{\cancel{V_{DS}}}{\mu_n C_{ox} \frac{W}{L} (V_{GS} - V_{TH}) \cancel{V_{DS}}}$$
$$= \frac{1}{\mu_n C_{ox} \frac{W}{L} \underbrace{(V_{GS} - V_{TH})}_{\text{overdrive voltage}}}$$

So, MOSFET operate as resistor
whose value is controlled by
 $(V_{GS} - V_{TH})$ i.e. overdrive voltage.

remember condition:
 $V_{DS} \ll 2(V_{GS} - V_{TH})$

\hookrightarrow MOS device may be 'ON' even

if it carries no current.
device operates in "deep triode region"



$$\underline{V_{DS} \ll 2(V_{GS} - V_{TH})}$$